Publisher's Note: Crucial role of interlayer distance for antiferromagnet-induced perpendicular magnetic anisotropy [Phys. Rev. B 92, 214435 (2015)]

Bo-Yao Wang, Po-Han Lin, Ming-Shian Tsai, Chun-Wei Shih, Meng-Ju Lee, Chun-Wei Huang, Nae-Yeou Jih, Pei-Yu Cheng, and Der-Hsin Wei

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This paper was published online on 28 December 2015 with an error in Fig. 3. Figure 3 has been replaced as of 25 May 2016. The figure is incorrect in the printed version of the journal; therefore for the benefit of the print readership, the figure and its caption are replicated below.

FIG. 3. (a) Selected LEED specular spot I/V curves for various Mn films grown on the 1–3 ML Co/14 ML Ni/Cu(001) films measured at 300 K (RT). (b) Average interlayer distance ($d_{\perp}$) of various films calculated according to the energy peaks (I) in the I/V curves at RT or 150 K (LT). The $d_{\perp}$ of the Mn films changed from approximately 1.71 to 1.88 Å when $t_{Mn} > 6$ ML. In (b), the dashed line at the bottom represents $d_{\perp}$ of the 1–3 ML Co films grown on Cu(001); the dotted line at the top shows the $d_{\perp}$ of the fcc-Mn films grown on Cu₃Au(001) [11]. The crystalline structures of the c-fct Mn and e-fct Mn films, determined from the LEED and LEED I/V analysis, are shown at the top.